

A Roadmap for Heterogeneous Integration for the Next Decade and Beyond An Academic Perspective

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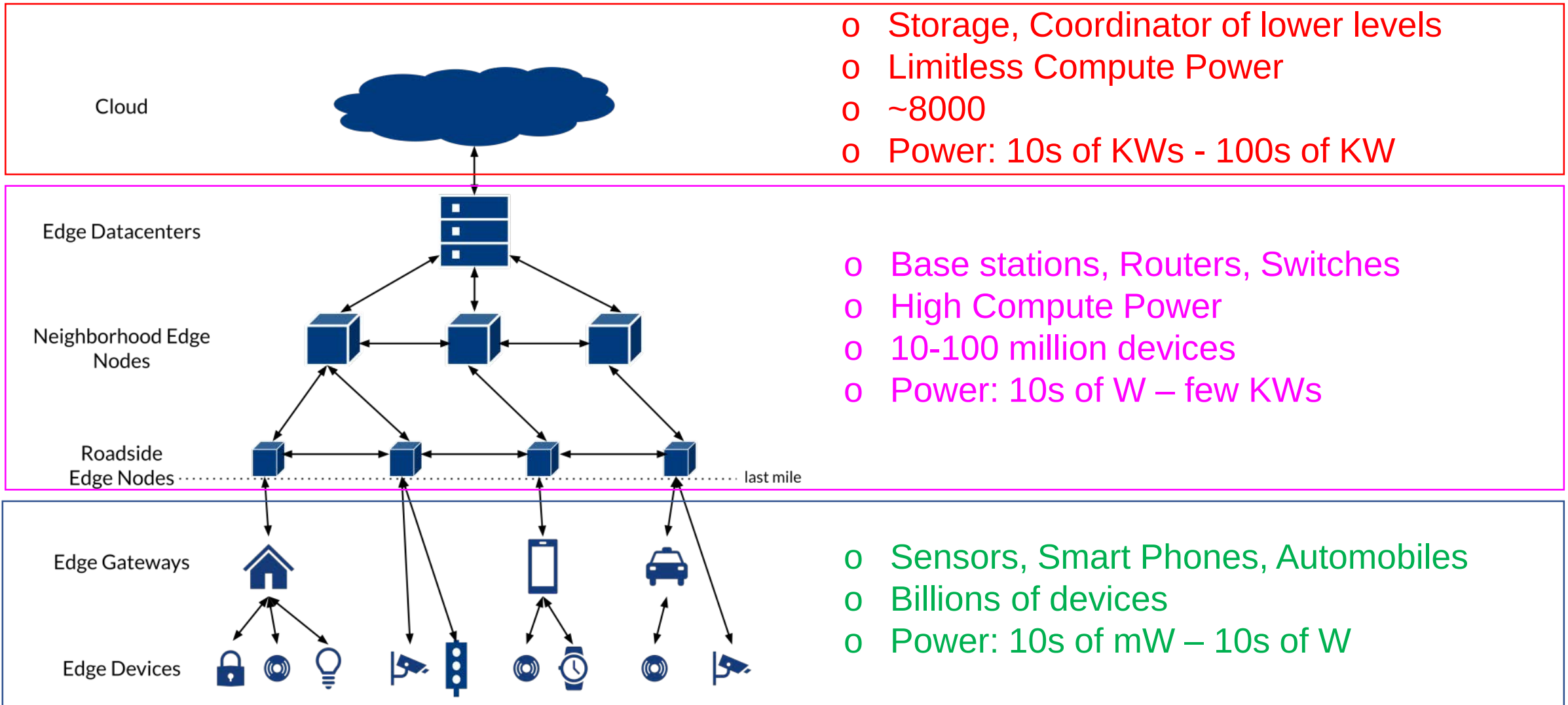
Outline

- ❑ Emerging Applications
- ❑ Need for Heterogeneous Integration
- ❑ A 10 Year and Beyond Roadmap
- ❑ CHIMES – A Snap Shot

Emerging Applications

- ☐ Cognition (AI)
- ☐ Communication (C)
- ☐ Sensing (S)
- ☐ Distributed Computing (DC)
- ☐ Intelligent Memory (M)
- ☐ Harsh Environments (H)

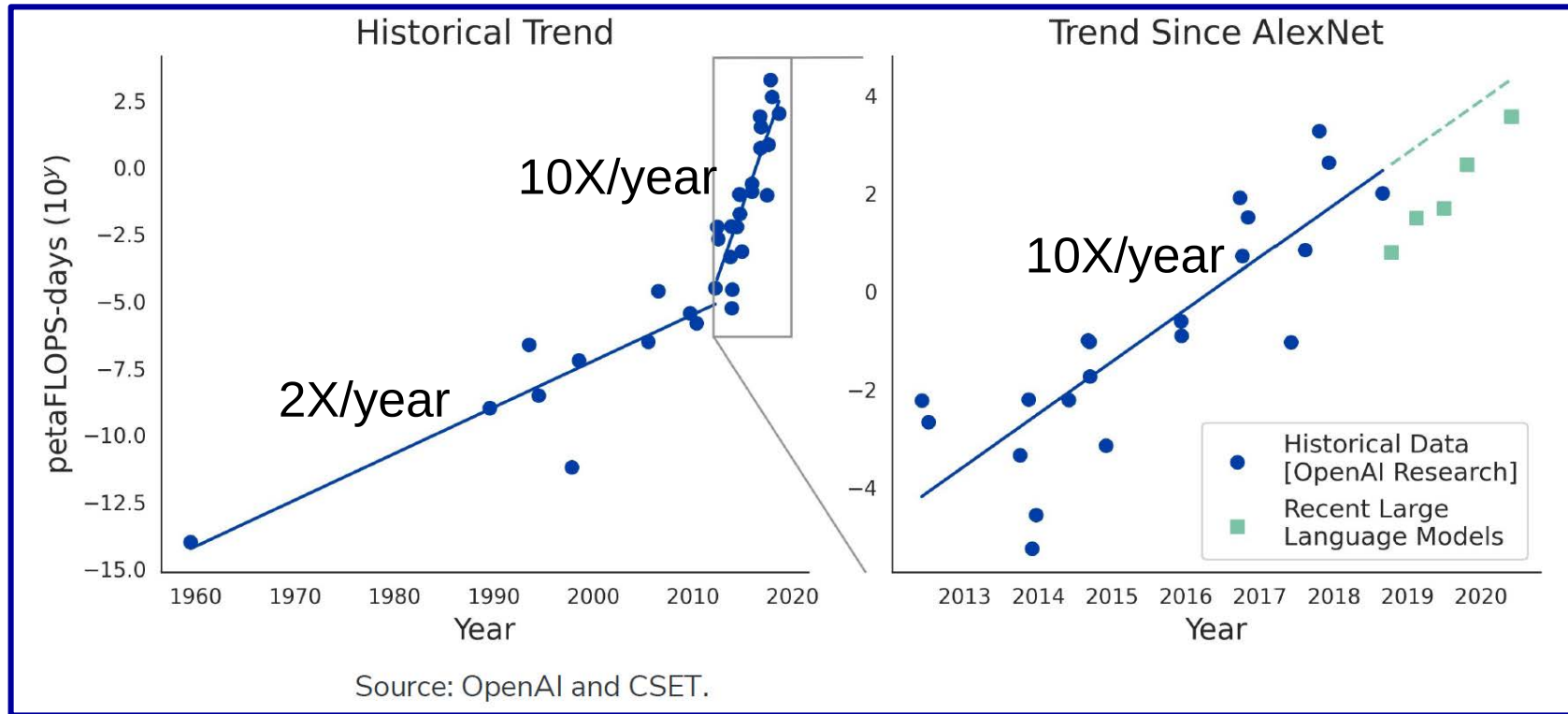
Emerging Distributed & Edge Computing



Ref: Jeff Burns, "Systems and Architectures for Distributed Compute", SRC Workshop, 2022.

<https://www.inovex.de/de/blog/edge-computing-introduction/>

Deep Learning & Computational Power (Large Data Centers)

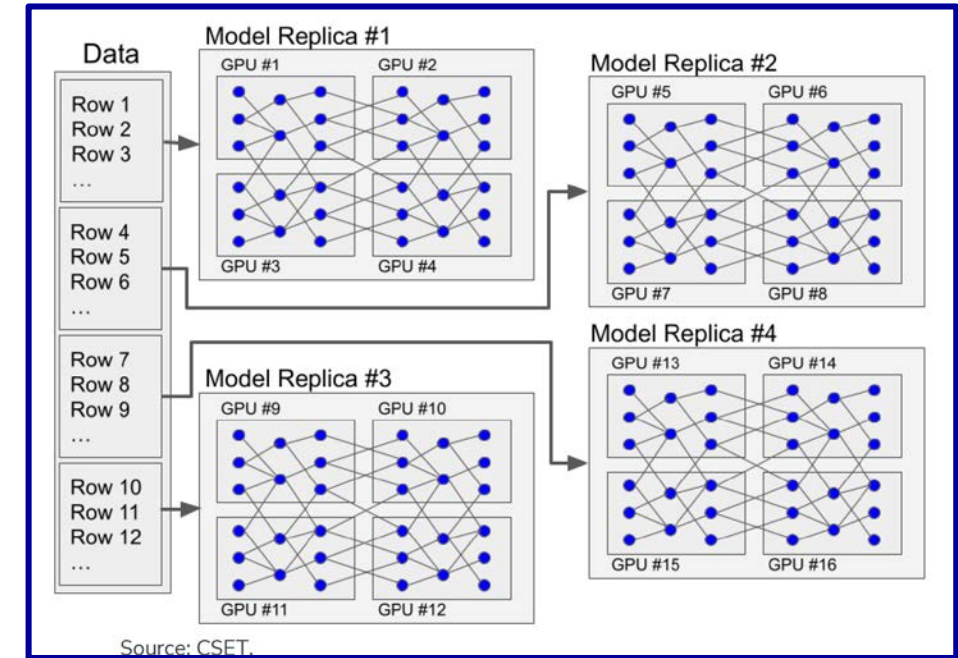
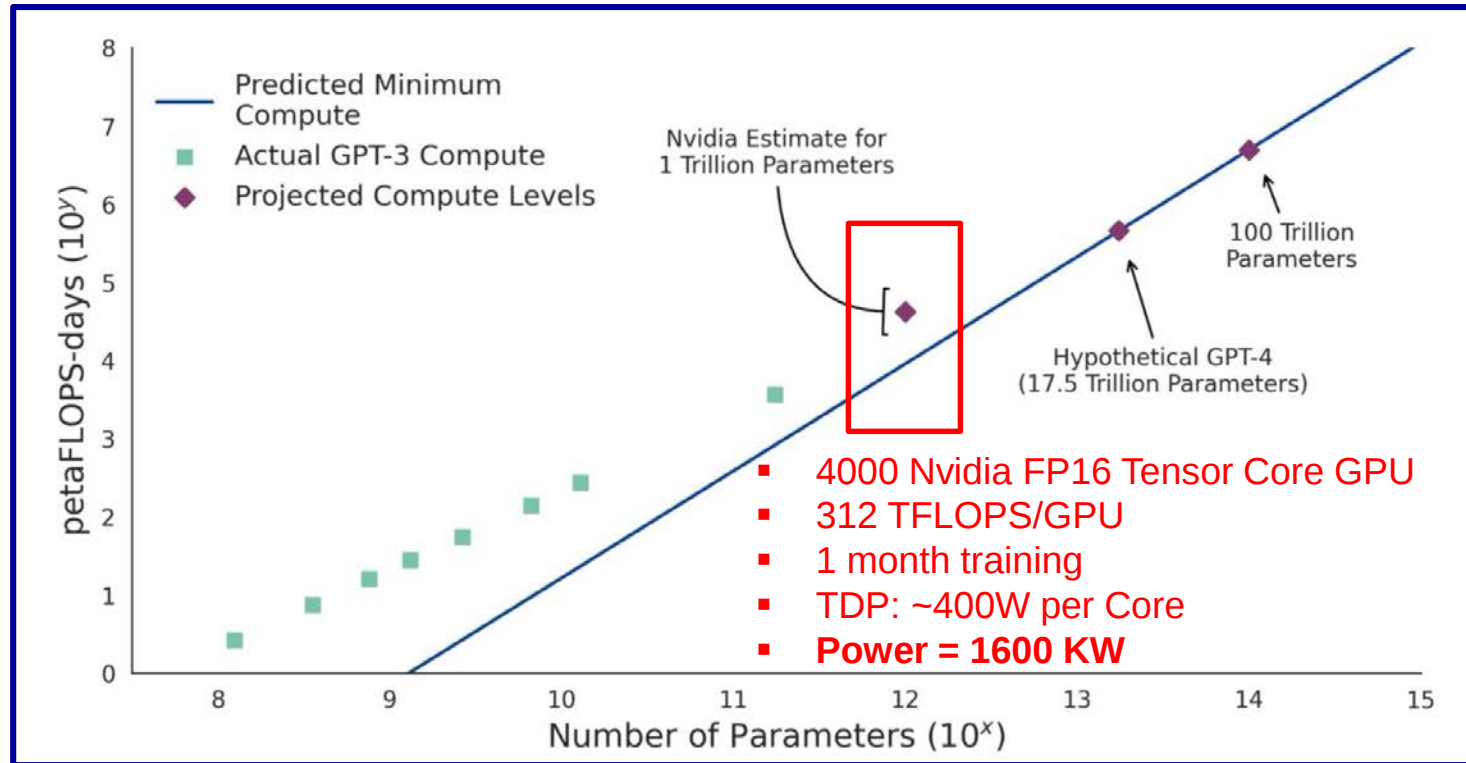


□ Observations

- Prior to 2012: Compute demand doubling every 2 years at the same rate as Moore
- Since 2012: Compute demand growing 10X/year due to Deep Learning

Ref: Andrew John and Micah Musser, "AI and Compute – How much longer can computing power drive artificial intelligence progress", CSET, 2022

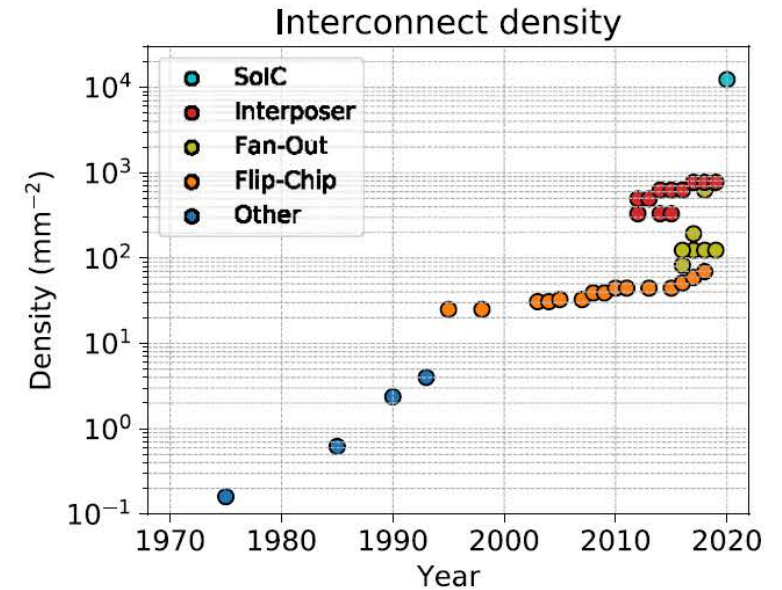
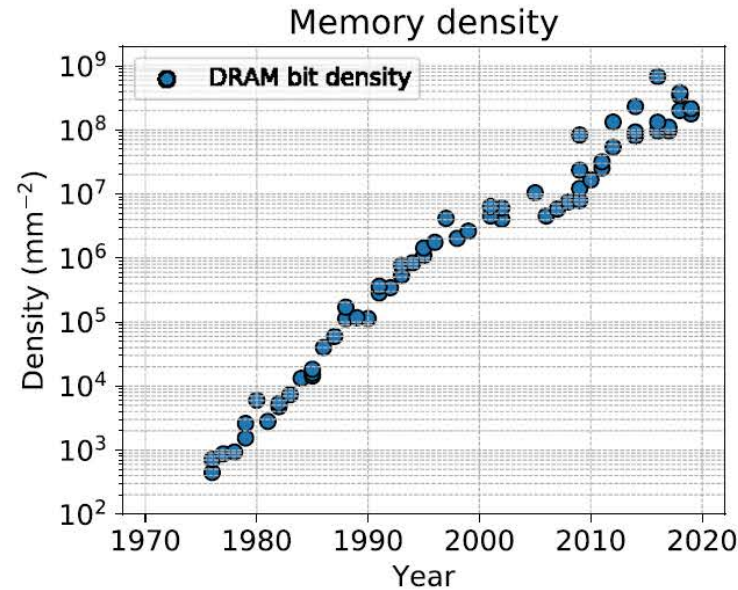
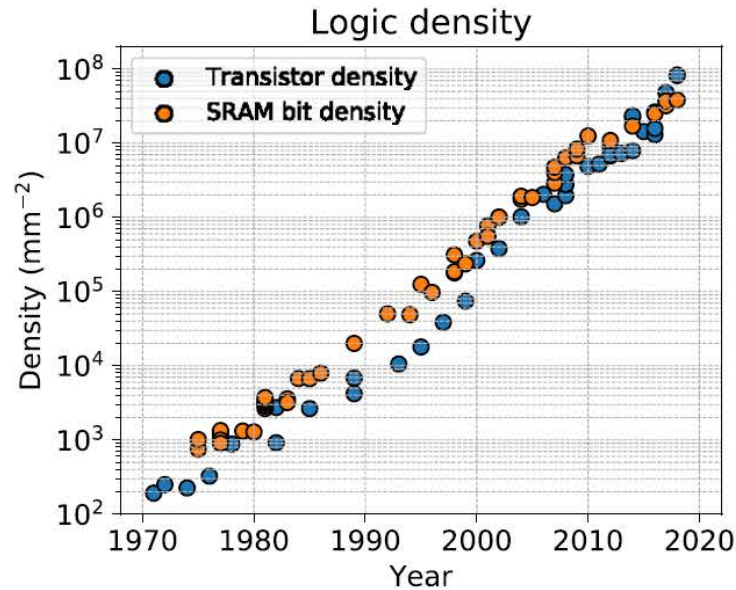
Compute Power & Scaling



- 2X Process Gains (8nm)
- 3X Architecture Gains (Tensor Flow)
- 300X System Scale out (Data Centers) – OUCH!
- Energy crisis if we continue on this path

Ref: Andrew John and Micah Musser, "AI and Compute – How much longer can computing power drive artificial intelligence progress", CSET, 2022
Anna Herr and Quentin Herr, Superconducting AI & HPC, IMEC

Historical Trends & Future (Estimated) Needs



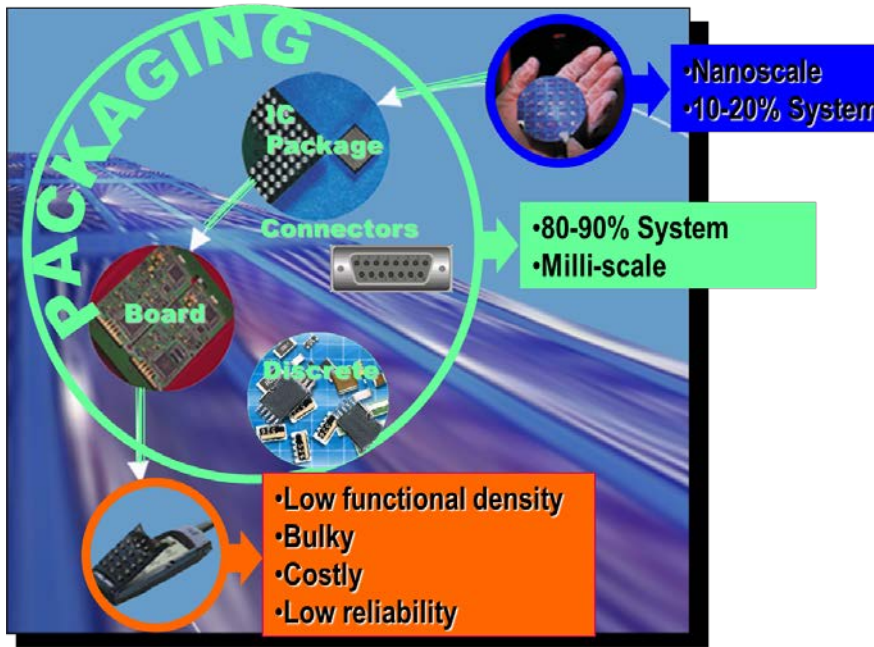
H.-S. Philip Wong, et al, "A Density Metric for Semiconductor Technology", Proceedings of the IEEE, April 2020

Current State of the Art

- Monolithic logic 10^8 transistors/ mm^2
- DRAM 10^9 transistors/ mm^2
- IO density 10^4 IO/ mm^2
- SRAM Access 20-50 TBps

10-100X increase in transistor densities
Interconnect densities 10^6 and higher (100X)
Energy per bit (EPB) reduced to femto-joules/bit
500TBps/ mm^2 of bandwidth (10X increase)
Wireless communication at 1Tbps

Is Heterogeneous Integration the Answer?



Packaging (Past)



Advanced Packaging (Present)



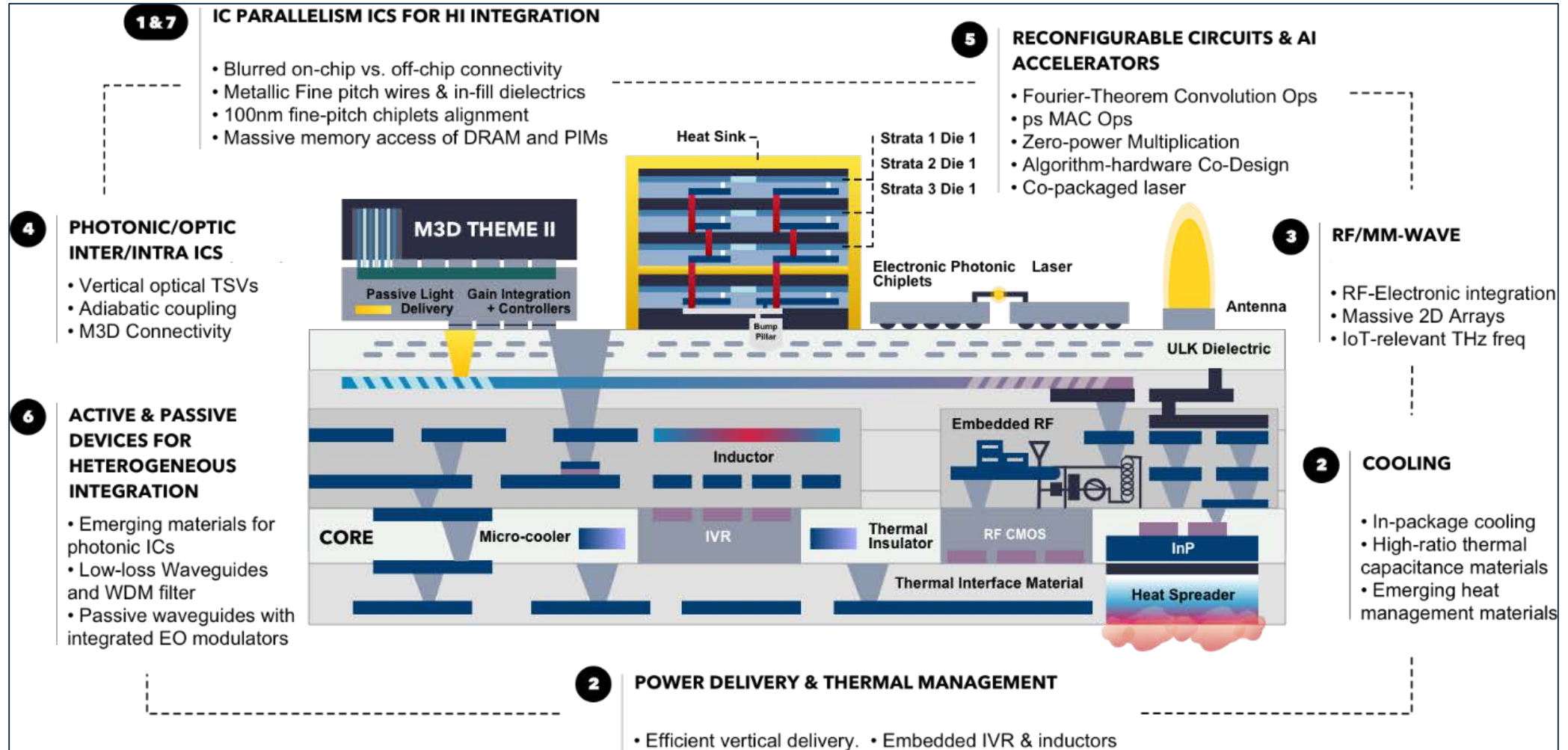
Heterogeneous Integration (Future)

- ❑ **Past/Present:** FEOL Transistor, BEOL Wiring & Package individually developed and combined
- ❑ **Future:** New and transformative logic, memory, and interconnect technologies that overcome the inevitable slowdown of traditional dimensional scaling of CMOS by interconnecting a **diversity of transistors and integrated circuit components, blurring the line between what is on-chip and what is off-chip.**

Grand Challenges

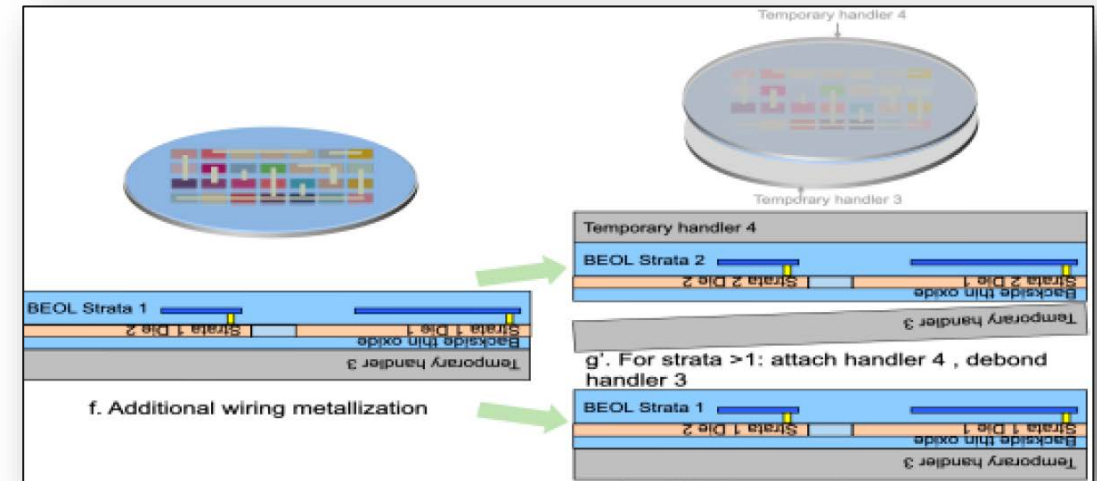
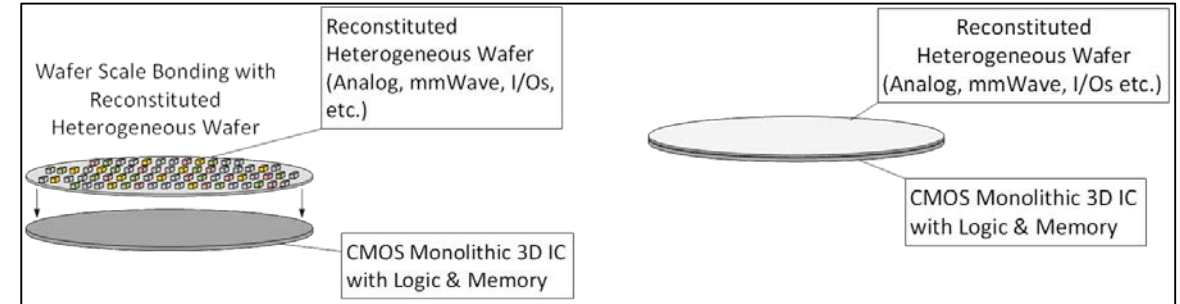
1. Heterogeneous integrated systems with volumetric transistor and interconnect densities approaching monolithic integration through 250-nm pitch self-aligned chip I/Os, and massive and seamless photonic connectivity with bandwidth density of 100Tbps/mm.
2. A generalized framework for materials synthesis and implementation with optimized properties.
3. Power management with segmented and deeply integrated power delivery solutions at 50kW with >80% efficiency.
4. Ultra-compact multi-scale thermal management solutions for densely integrated electronic, photonic, and sub-Terahertz components with micron-scale heat spreaders for $>1\text{ kW/cm}^2$ heat flux, and superior energy efficiency and reliability.
5. Reconfigurable photonic interconnects enabling adaptive & optimized system configurations achieving > 100X enhancement in energy-efficiency and throughput compared to SOTA.
6. Fully integrated electronics, photonics and thermal design automation platform.

Ultra-dense Heterogeneous Platform – A Futuristic Outlook



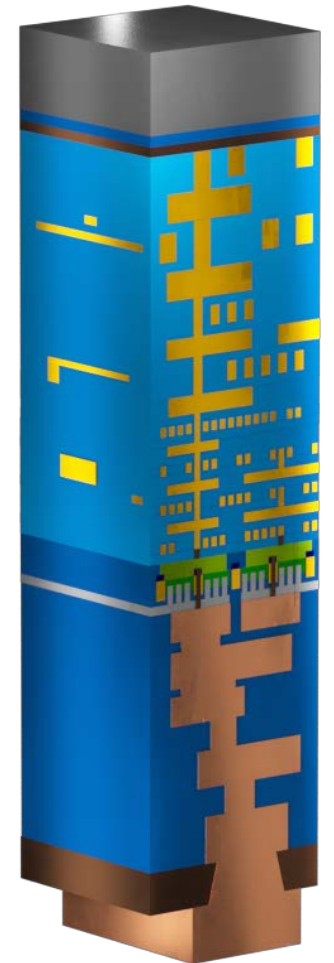
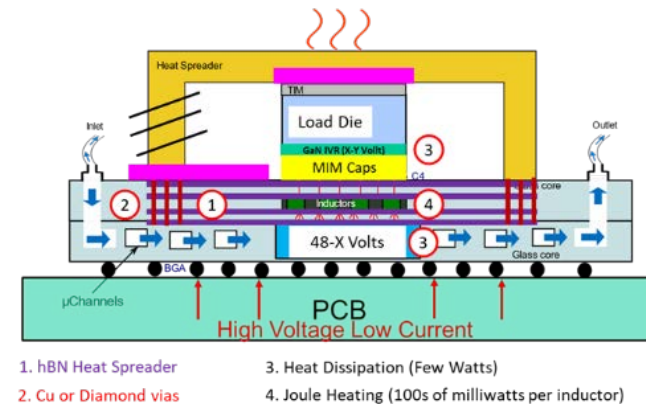
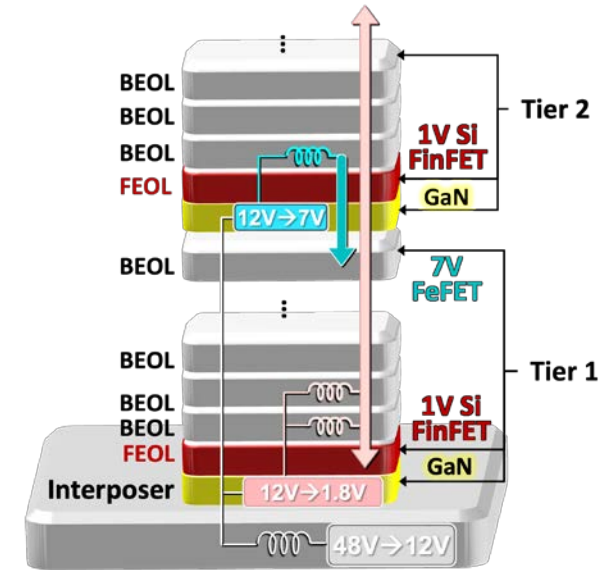
The Roadmap - Volume Scaling

Metric & Drivers	Metric (10 Years)	State of the Art (SOTA)
Electrical IC Parallelism & Volume Scaling (AI, DC, M)	IO density 16M/mm ²	IO density 10K/mm ²
	BW Density > 500Tbps/mm ² ; <0.01 pJ/bit	BW density 28Tbps/mm ² ; 0.021 pJ/bit (ARM/GT IEDM 2020)
Cooling & Power Delivery (S, C, H, AI)	Power 1000W; Current density 2–5A/mm ² ; Efficiency >80% (HIR 10 year)	Power 400W; Current Density 1A/mm ² ; Efficiency <70%
	Current 50 Kamps; Power 50kW; PDN Power <1KW (2%); Efficiency>80%	Current 18 Kamps; Power 10KW; PDN 5KW (33%); η <67% (Tesla Dojo)
Wireless IC & I/O (C, S, H)	Insertion Loss <1dB (PA output to Antenna input) @ 0.3 – 1THz; DARPA ELGAR 1dB	Insertion Loss >5dB in D-Band (110–170 GHz) (ComSenTer)
	Antenna efficiency >90% @ 0.3–1THz	Antenna efficiency >90% (< 100GHz)
	SNR 30dB (128 QAM)	SNR 20dB (128 QAM) D-Band
Photonic/Optic IC and Chiplet Communication (AI, C, DC)	Coupling loss < 0.9dB; Misalignment; +/-1mm	Coupling Loss ~ 1dB (O-Band)
	100 (Tbps/mm)/(pJ/bit) (link-level)	1 (Tbps/mm)/(pJ/bit) (DARPA PIPES)
	Bandwidth (BW) Reconfigurable ICs between chiplets; 0.5-5Tbps aggregated BW	NA
Reconfigurable Circuits & Modules (AI, S, DC)	Optical gain/laser integration via photonic wire bonds (PWB) and/or mono-int. (DARPA LUMOS)	Laser is off-chip → requiring packaging (costly & not reliable)
	100 TOP/J, 1ns latency, infinite bit-resolution MAC ops (DOD Labs e.g., AFRL, ARL)	<5 TOP/J, 1000+ns latency, 4-12 bit
Active & Passive Devices for Heterogeneous Integration (C, S, DC)	AI accelerator: 10–100 fJ/MAC, 1–50 TMACs/mm ² , 1ns–25 ps operation (Google X)	0.5–1 pJ/MAC, 0.5–1 TMAC/s/mm ² , 0.5–1 GMVM/s, and 1–2 us per MVM
	EO Modulator: ER > 12dB; BW > 15GHz per channel; (next Gen AIM Photonics components)	NA
	Interposer Waveguides; losses < 0.1dB/cm	1.5dB/cm
	Interposer Filters for WDM: filter sharpness > 15dB over < 0.2nm BW (AIM Photonics Foundry)	NA



The Roadmap - Addressing the Current Problem

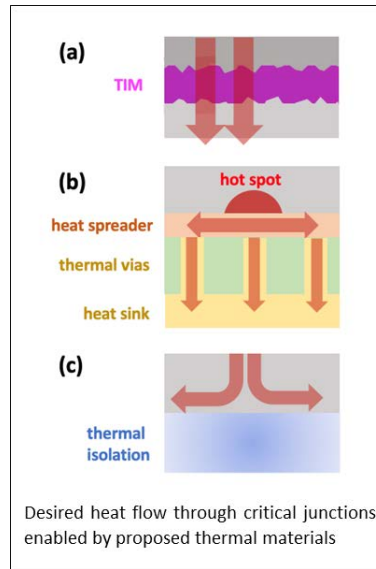
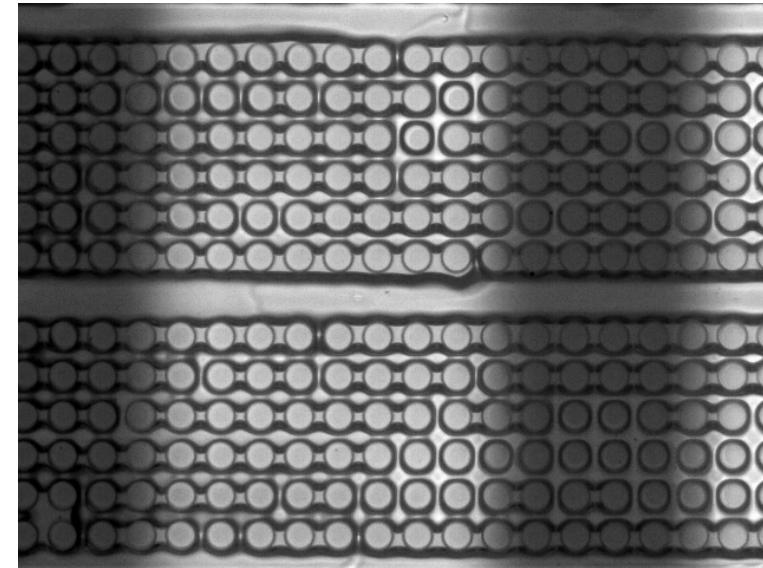
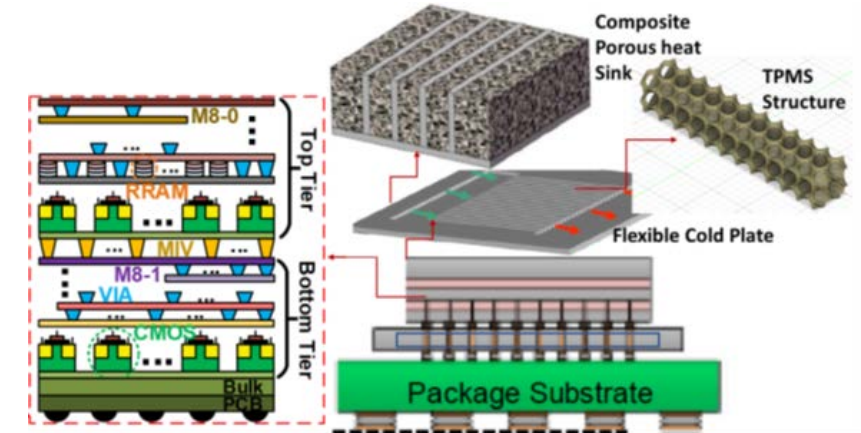
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	Current 50 Kamps; Power 50kW; PDN Power <1KW (2%); Efficiency>80%	Current 18 Kamps; Power 10KW; PDN 5KW (33%); η <67% (Tesla Dojo)
Wireless IC & I/O (C, S, H)	Insertion Loss <1dB (PA output to Antenna input) @ 0.3 – 1THz; DARPA ELGAR 1dB	Insertion Loss >5dB in D-Band (110–170 GHz) (ComSenTer)
	Antenna efficiency >90% @ 0.3–1THz	Antenna efficiency >90% (< 100GHz)
	SNR 30dB (128 QAM)	SNR 20dB (128 QAM) D-Band
Photonic/Optic IC and Chiplet Communication (AI, C, DC)	Coupling loss < 0.9dB; Misalignment; +/-1mm	Coupling Loss ~ 1dB (O-Band)
	100 (Tbps/mm)/(pJ/bit) (link-level)	1 (Tbps/mm)/(pJ/bit) (DARPA PIPES)
	Bandwidth (BW) Reconfigurable ICs between chiplets; 0.5-5Tbps aggregated BW	NA
Reconfigurable Circuits & Modules (AI, S, DC)	Optical gain/laser integration via photonic wire bonds (PWB) and/or mono-int. (DARPA LUMOS)	Laser is off-chip → requiring packaging (costly & not reliable)
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Active & Passive Devices for Heterogeneous Integration (C, S, DC)	AI accelerator: 10–100 fJ/MAC, 1–50 TMACs/mm ² , 1ns–25 ps operation (Google X)	0.5–1 pJ/MAC, 0.5–1 TMAC/s/mm ² , 0.5–1 GMVM/s, and 1–2 us per MVM
	EO Modulator: ER > 12dB; BW > 15GHz per channel; (next Gen AIM Photonics components)	NA
	Interposer Waveguides; losses < 0.1dB/cm	1.5dB/cm
	Interposer Filters for WDM: filter sharpness > 15dB over < 0.2nm BW (AIM Photonics Foundry)	NA



Courtesy: K. Radhakrishnan, Intel

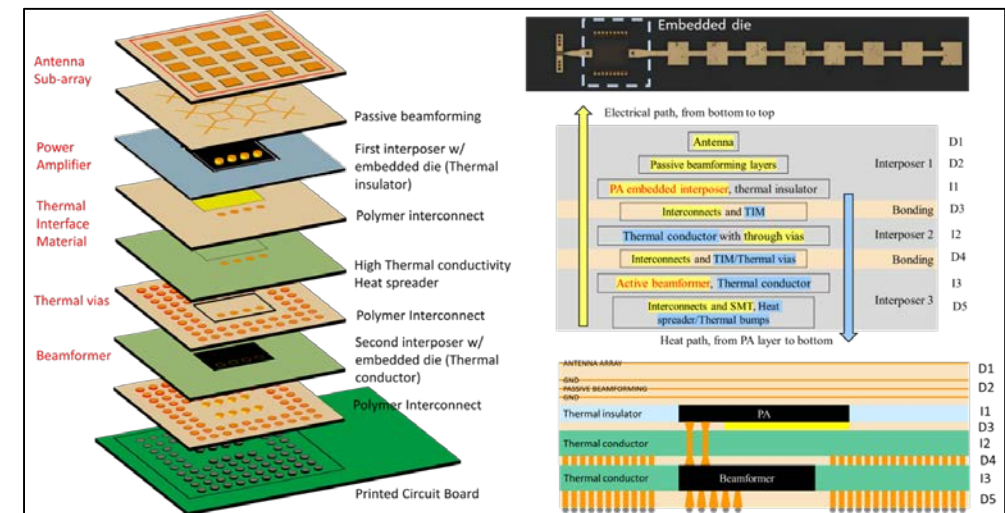
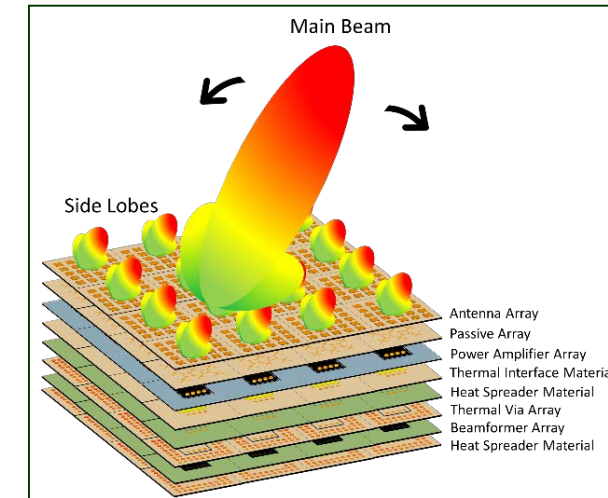
The Roadmap - Staying Cool

Metrics & Drivers	Metrics (10 Years)	State of the Art (SOTA)
Benchmarking (AI, C, S, DC, M, H)	Automated cross-layer pathfinding framework with Power, Performance, Form-factor, Cost and Reliability (PPFCR) prediction for full systems + applications.	Pathfinding limited to technology or technology + circuit only; limited automation.
Co-Design (AI, C, S, DC, M, H)	Physical design tools for M3D chiplets integrated on systems spanning > 20,000mm ²	No tools for M3D; interposer tools limited to ~2000mm ²
Power Delivery (AI, DC, H)	Power 1000W; Current density 2-5A/mm ² ; Efficiency >80% (HIR 10 year)	Power 400W; Current density 1A/mm ² ; Efficiency <70%
	Current 50 kAmps; Power 50kW; PDN Power <1kW (2%); Efficiency >80%	Current 18 kAmps; Power 10kW; PDN 5kW (33%); Efficiency <67% (Tesla Dojo)
Thermal (AI, C, DC, H)	Chiplet: Background heat flux (entire die) 2kW/cm ² ; hot spot heat flux (0.1mm x 0.1mm) 30kW/cm ² ; Vol. removal 2kW/cm ² mm; Thermal time constant 1μs	Background heat flux (entire die) 200W/cm ² ; hot spot heat flux (1mm x 1mm) 1kW/cm ² ; Vol. removal 200W/cm ² mm; Thermal time constant 20μs
	Stack: Thermal isolation ratio 0.95; TIM specific resistance 0.3 mm ² K/W for 30 μm; k 200 W/mK, elastic modulus 30 MPa	Thermal isolation ratio 0.5; TIM specific resistance 1 mm ² K/W (DARPA NTI)
	Interposer: Heat spreader effective k 10,000 W/mK; Heat spreader thickness 0.2mm	Heat spr. effective k 4000 W/mK; Heat spreader thickness 2mm (DARPA TGP)
	Server (1U): Volumetric R _{th} 0.015 °Ccm ³ /W	Volumetric R _{th} 0.03 °Ccm ³ /W
Electrical/Optical Test (AI, DC)	Fault coverage >99% (Short/Open) & >95% (device/components)	<95% coverage (Short/Open), devices/components (no test or BIST)
	10X reduction in test cost (Package BIST)	(Relative) test cost growing
Hardware Security	Probability of trojan evasion >99%	No universal security metrics available
	Probability of reverse engineering <1%	No universal security metrics available
	Split manufacturing based on fine pitch HI	Not available



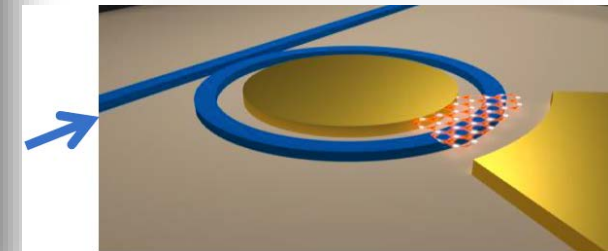
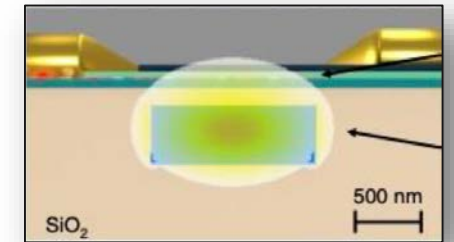
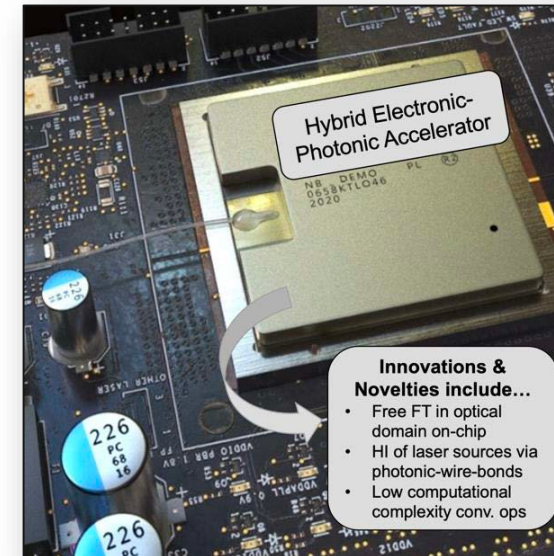
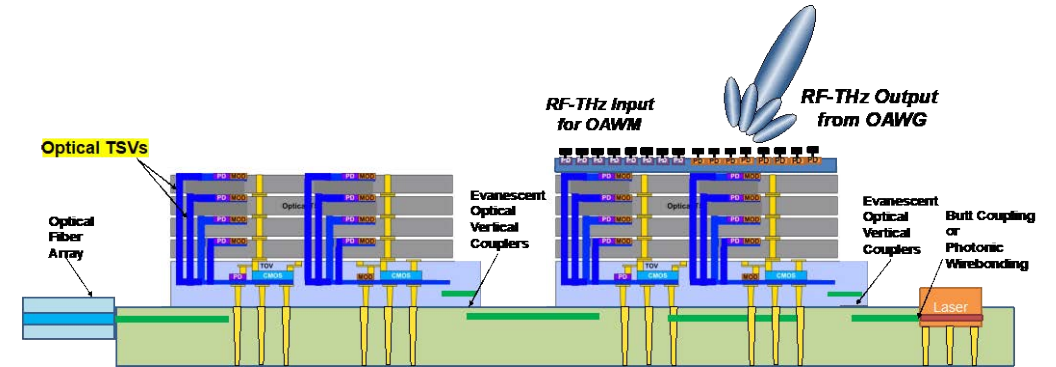
The Roadmap - Ensuring Connectivity the Wireless Way

Metric & Drivers	Metric (10 Years)	State of the Art (SOTA)
Electrical IC Parallelism & Volume Scaling (AI, DC, M)	IO density 16M/mm ²	IO density 10K/mm ²
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Wireless IC & I/O (C, S, H)	Insertion Loss <1dB (PA output to Antenna input) @ 0.3 – 1THz; DARPA ELGAR 1dB	Insertion Loss >5dB in D-Band (110–170 GHz) (ComSenTer)
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	100 (Tbps/mm)/(pJ/bit) (link-level)	1 (Tbps/mm)/(pJ/bit) (DARPA PIPES)
	Bandwidth (BW) Reconfigurable ICs between chiplets; 0.5-5Tbps aggregated BW	NA
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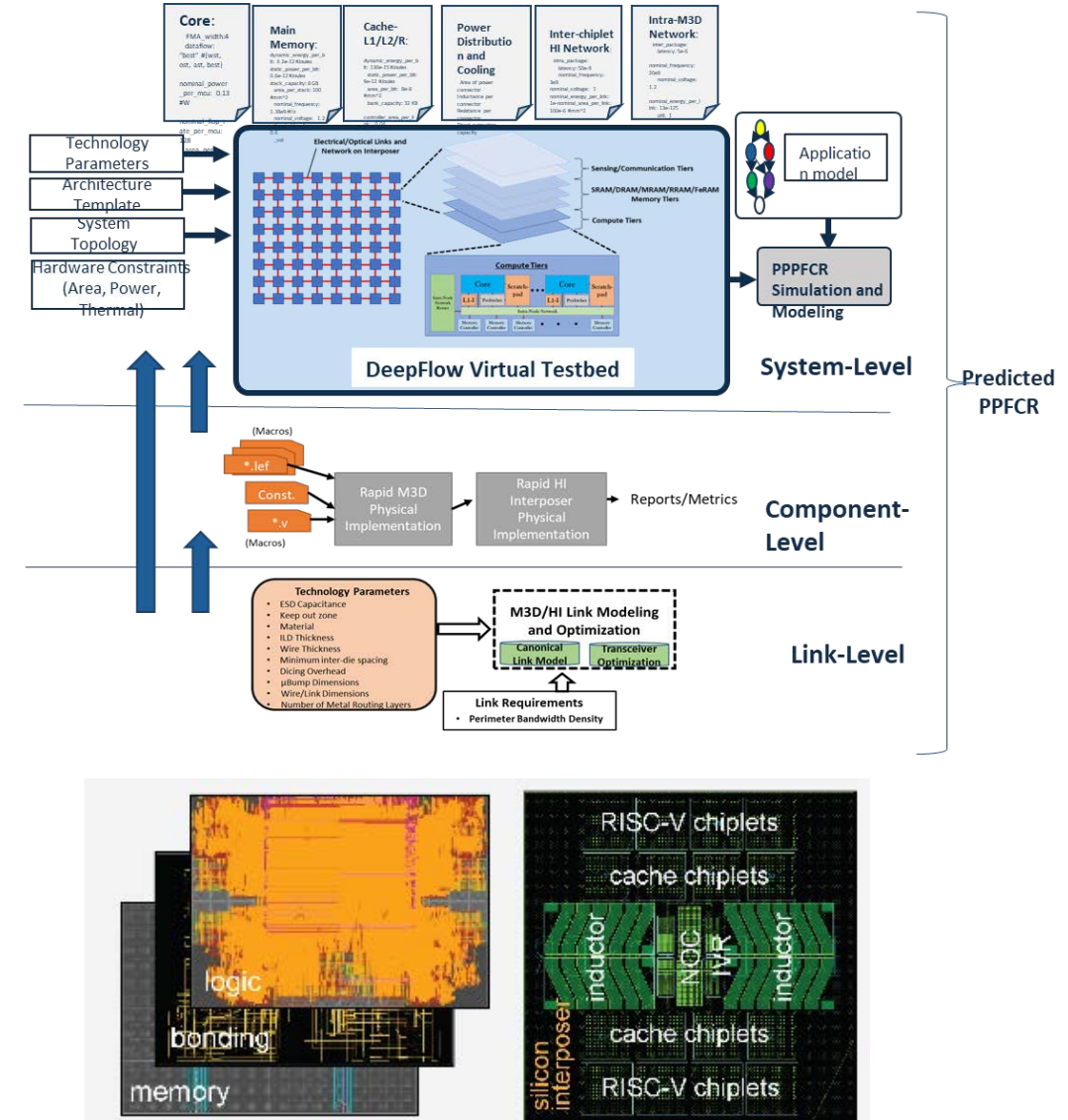
The Roadmap – Lighting it up

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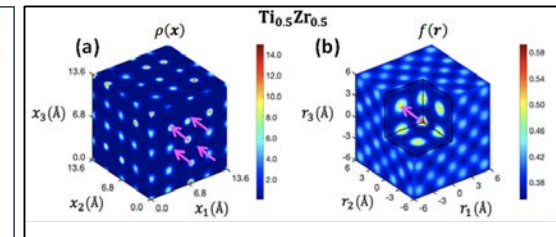
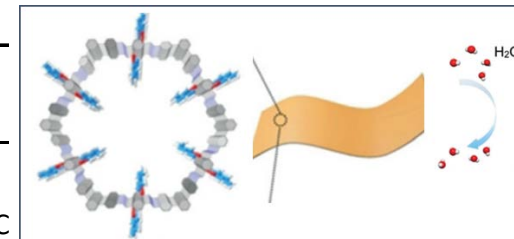
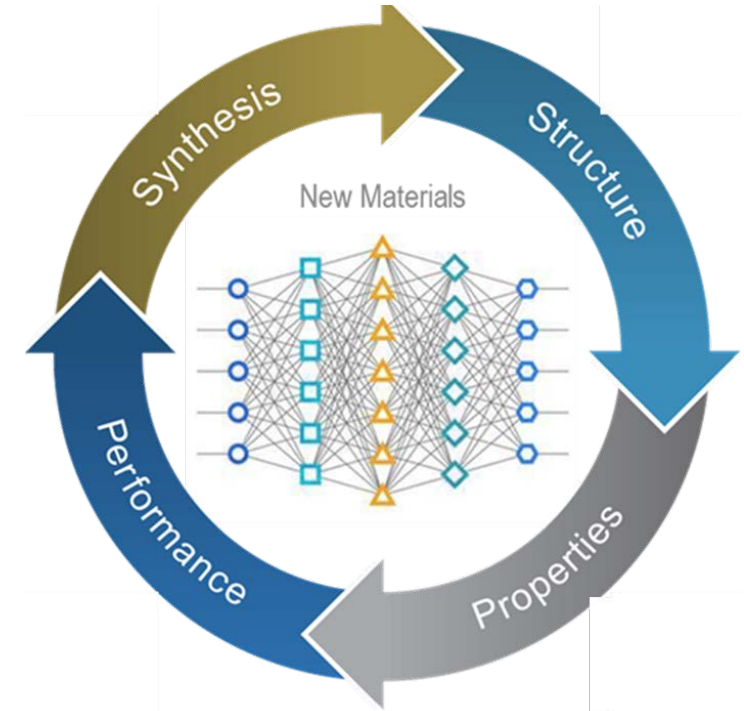
The Roadmap – Democratizing Heterogeneous Integration

Metrics & Drivers	Metrics (10 Years)	State of the Art (SOTA)
Benchmarking (AI, C, S, DC, M, H)	Automated cross-layer pathfinding framework with Power, Performance, Form-factor, Cost and Reliability (PPFCR) prediction for full systems + applications.	Pathfinding limited to technology or technology + circuit only; limited automation.
Co-Design (AI, C, S, DC, M, H)	Physical design tools for M3D chiplets integrated on systems spanning > 20,000mm ²	No tools for M3D; interposer tools limited to ~2000mm ²
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	Stack: Thermal isolation ratio 0.95; TIM specific resistance 0.3 mm ² K/W for 30 μm; k 200 W/mK, elastic modulus 30 MPa	Thermal isolation ratio 0.5; TIM specific resistance 1 mm ² K/W (DARPA NTI)
	Interposer: Heat spreader effective k 10,000 W/mK; Heat spreader thickness 0.2mm	Heat spr. effective k 4000 W/mK; Heat spreader thickness 2mm (DARPA TGP)
	Server (1U): Volumetric R _{th} 0.015 °Ccm ³ /W	Volumetric R _{th} 0.03 °Ccm ³ /W
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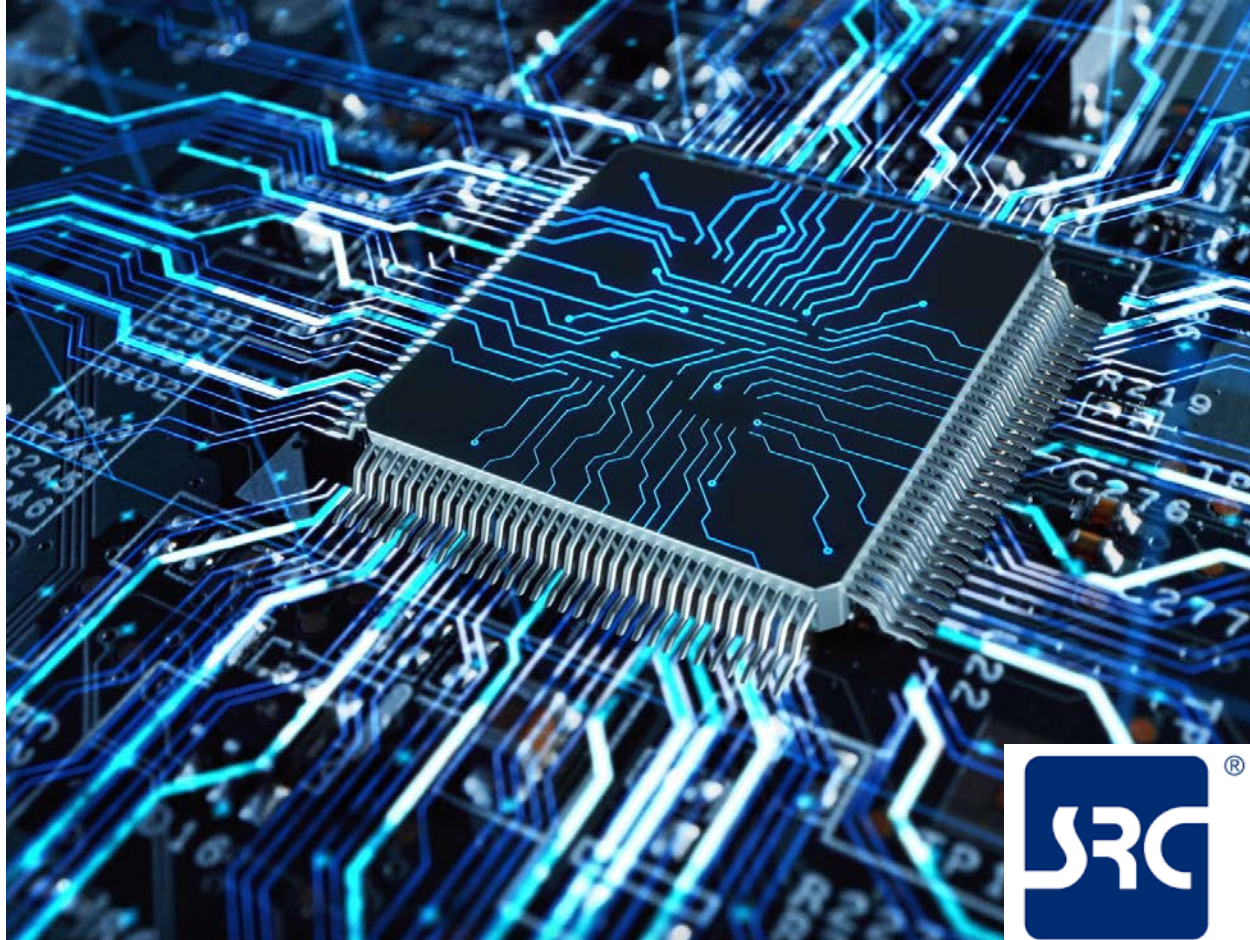
The Roadmap – We live in a Material World

Metrics & Drivers	Metrics (10 Years)	State of the Art (SOTA)
Ultra-low K Dielectrics (Al, C, DC, M)	Permittivity < 2.5, Loss 0.01 @ 1THz, Thickness: 1 μ m – 100 μ m, CTE: <30 ppm/C	Permittivity 3.0, Loss 0.05 @ 150GHz, Thickness: 5mm, CTE: 30-40 ppm/C
Interconnects (Al, DC, M)	For BEOL Devices: 100nm pitch, 50nm dia., aspect ratio 2-10 for 2-5 tiers for via bottom-up fill.	400nm pitch, 200nm dia., aspect ratio up to 5 (selective ALD for Co from ASCENT)
	TSVs: 100 nm diameter, 250 nm pitch; aspect ratios >30:1	9 μ m pitch and $\sim$ 2 μ m diameter [AMD 3D V-cache]
Thermal (Al, C, S, DC, H)	Misalignment-tolerant bonding process for inter-layer interconnects at 250 nm pitch	5.5 μ m pitch using face-to-face hybrid bonding [ARM/GF]
	TIM: 200W/m-K; Thickness <30 μ m; CTE 20 ppm/C	TIM: 25-100 W/m-K; CTE 55-200 ppm/C
	Heat Spreader: - cBN 200 W/mK at 100 nm thick, 500W/mK at 1 μ m - Diamond 400 W/mK at 1 μ m, 1500 W/mK at 10 μ m, 2000 W/mK at 50 μ m.	Heat Spreader: Cu 400 W/mK bulk
	Ultra-low interface thermal resistance, e.g. GaN/diamond 3 m ² K/GW, Si/diamond 3 m ² K/GW	GaN/diamond 6.5 m ² K/GW Si/diamond 9.5 m ² K/GW
	Thermal isolation materials: 0.02 W/m-K, dielectric constant < 1.5, thermally stable above 300°C	Thermal isolation materials (SiCOH): 0.6 W/m-K, dielectric constant 1.8-2.5, and thermally stable above 300°C



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- Center for Heterogeneous Integration of Micro Electronic Systems (CHIMES)
- Supported by the Semiconductor Research Corporation (SRC)'s Joint University Microelectronics Program 2.0 (JUMP 2.0), a consortium of industrial partners in cooperation with the Defense Advanced Research Projects Agency (DARPA)



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The CHIMES Team



